

## WHAT YOU WILL EXPERIENCE

This 2-day hands-on course is designed for SysML v1 practitioners and technical leaders who want to gain practical experience with the graphical aspects of SysML v2 as implemented in most current version of the CATIA Magic tools. Participants will learn how SysML v2 builds on and improves v1 concepts, with a focus on key differences in structure, syntax, and modeling approaches. While the course will introduce how graphical models map to the SysML v2 textual language, the primary emphasis will be on building models using the graphical interface in the CATIA family of products. Through guided exercises, attendees will explore v1-to-v2 modeling transitions, understand the value proposition of SysML v2, and develop foundational skills for applying the current SysML v2 capabilities in CATIA Magic to pilot projects or early-stage efforts.

## WHAT YOU WILL GAIN

- Gain insight into the graphical modeling capabilities of SysML v2 supported by CATIA Magic tools
- Understand key conceptual and syntax differences between SysML v1 and v2
- Learn how graphical models transition to textual representations in SysML v2
- Understand basic considerations for tool migration and process adaptation when adopting SysML v2
- Build basic SysML v2 graphical models using CATIA Magic products
- Differentiate between replicating v1-style modeling and using SysML v2's graphical approach

## WHO SHOULD JOIN

This course is designed for SysML v1 Modelers looking to expand their modeling capabilities with CATIA Magic's SysML v2 implementation and early adopters seeking hands-on experience with the graphical SysML v2 environment.

## WHAT YOU WILL NEED

A computer with a large screen or external monitor; ideally two screens. Microsoft teams and the capability to run CATIA Magic Software - Participants must have the latest version of CATIA Magic with SysML v2 installed, or they may use one of our provided academic licenses during the course.









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